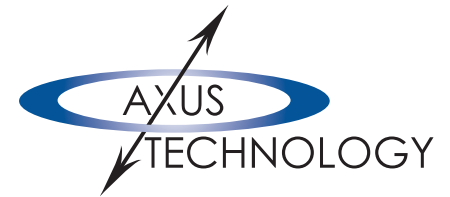


AQUARIUS

A200-sa

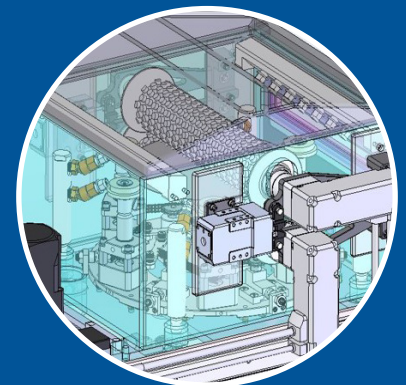
POST CMP WAFER CLEANER



Your source for leading-edge surface processing solutions

KEY COMPETITIVE ADVANTAGES

- Can be configured to run two different wafer sizes simultaneously
- Fully independent wafer and brush rotation control
- Top or bottom brush can rotate in either direction at any speed
- Brush compression can be controlled by 3 different metrics: position, torque, and force
- Controlled clamping force for fragile wafers in both spin and brush boxes.
- Two chemicals can run diluted or concentrated with optional on-board dilution capabilities.
- Integrated wafer flipping, nozzle megasonics, and flat finder/OCR (optional)



Aquarius Brush Box

The new and innovative Axus Technology Aquarius Wafer Cleaner provides improvements in all aspects of 100mm, 150mm, and 200mm wafer cleaning, including defectivity and throughput.

Features includes:

- Four brush boxes with full recipe control of all critical process variables
- Two spin-rinse-dry stations
- Two wet cassette stations in and two dry stations out
- High speed wafer handling robot with dual end effectors
- All operations can be done manually from the graphical user interface
- Three different modes of control for brush/wafer contact: position, brush torque, and contact force

Dimensions: 70"W x 56"D x 98"H

7001 WEST ERIE STREET, SUITE 1, CHANDLER, ARIZONA 85226

480.705.8000 | AXUSTECH.COM

Aquarius A200-sa Rev 03 10 '21